MAY 1 6 2005

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No	10/624,716
Filing Date	July 21, 2003
Inventor	Luan C. Tran
	Micron Technology, Inc.
	2812
Examiner	Kennedy, Jennifer M.
	Ml22-2357
	Methods of Forming Semiconductor Constructions

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References -See Attached Form PTO-1449

The attached form PTO-1449 is submitted in compliance with 37 CFR §1.56. Copies of the cited art are included with the exception of U.S. patents and published U.S. applications (1276 OG 55). No admission is made regarding whether all the submitted references are prior art.

Respectfully submitted,

Dated:

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MAY 1 6 2005 (\$)				FILING DATE July 21, 2003			GROUP 2812			
A TRANSMIN			U.S. PA	TENT DOCUM	ENTS					
*Examiner Initial		Document Number	Date	Name		Class	Subclass	Filing Date If Appropriate		
	АА	5,534,456	07/96	Yuan et al.						
	AB	4,985,740	01/91	Shenai et al.						
	AC	5,904,530	05/99	Shin						
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	АН									
FOREIGN PATENT DOCUMENTS										
		Document Number	Date	Country	Class	Class	Subclass	Translat	tion	
				<u> </u>				Yes	No	
	AP	JP04105328A	04/92	Japan				Abstract		
	AQ		 							
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	AS		Wolf et al., "Silicon Processing for the VLSI Era, Vol. 1: Process Technology," Second Edition, Lattice Press 2000, pp.12-13, 25-27.							
	АТ		S.M. Sze, VLSI Technology, Second Edition, McGraw-Hill, 1988, pages 472-483							
EXAMINER			DATE CON	DATE CONSIDERED						
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP										

609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.